

Materials List for:

# Convergent Polishing: A Simple, Rapid, Full Aperture Polishing Process of High Quality Optical Flats & Spheres

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## Materials

Name	Company	Catalog Number	Comments
MHN 50 mil Polyurethane Pad	Eminess Technologies	PF-MHN15A050L-56	
Cerium oxide polishing slurry	Universal Photonics	HASTILITE PO	
Septum Glass (waterjet cut)	Borofloat ; Schott	NA	
Diamond conditioner	Morgan Advanced Ceramics	CMP-25035-SFT	
Ultrasonic Cleaner	Advanced Sonics Processing System	URC4	
Purification Optima Filter cartridge	3M	CMP560P10FC	
Blocking Pitch	Universal Photonics	BP1	
Blocking Tape	3M	#4712	
Cleanroom Cloth	ITW Texwipe	AlphaWipe TX1013	
Single Particle Optical Sensing	Paritcle Sizing Systems	Accusizer 780 AD	